



In re Application of:  
Bencher, et al.

**Group Art Unit: Unknown**

Examiner: Unknown

**For: A Silicon Carbide  
Deposition For Use As A  
Low Dielectric Constant  
Anti-Reflective Coating**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

I hereby certify that this correspondence is being deposited on January 23, 2004 with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450.

Date 01/13/2014 Signature Br. EL

Dear Sir:

The Applicants, and the Attorney who signs below on the basis of the information supplied by the inventor and the information in his file, submit herewith patents, publications, or other information of which they are aware, which may be material to the examination of this application and in respect of which there may be a duty to disclose in accordance with 37 CFR § 1.56.

While the information submitted in this Information Disclosure Statement may be material pursuant to 37 CFR § 1.56, it is not intended to constitute an admission that any patent, publication, or other information referred to therein is prior art for this invention unless specifically designated as such.

In accordance with 37 CFR § 1.97, this Information Disclosure Statement is not to be construed as a representation that a search has been made or that no other possibly material information as defined under 37 CFR § 1.56(a) exists.

The patents and/or publications submitted herewith are set forth on the attached Form PTO-1449.

If the sum of \$180.00 is due under 37 CFR § 1.17(p) pursuant to § 1.97, the Commissioner is hereby authorized to charge this fee, and any other fee necessary to make this submission timely, to the Deposit Account No.. 20-0782/AMAT/2966.C1/BKH.

Respectfully submitted,



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U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)		Docket No. AMAT/2966.C1/DSM /BCVD/JW	Serial No. 10/684,079
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)		Applicant Bencher, et al.	Confirmation No. Unknown
Examiner Unknown		Filing Date October 9, 2003	Group Unknown

**U.S. Patent Documents**

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
	A1	6,528,426	03/04/2003	Olsen, et al.	438	689	10/15/1999
	A2	6,514,667	02/04/2003	Angelopoulos, et al.	430	271.1	08/17/2001
	A3	6,445,073	09/03/2002	Zhao, et al.	257	771	01/02/1998
	A4	6,444,568	09/03/2002	Sundararajan, et al.	438	627	11/02/2000
	A5	6,316,167	11/13/2001	Angelopoulos, et al.	430	313	01/10/2000
	A6	6,245,662	06/12/2001	Naik, et al.	438	622	07/23/1998
	A7	6,159,871	12/12/2000	Loboda, et al.	438	786	05/29/1998
	A8	6,147,009	11/14/2000	Grill, et al.	438	780	06/29/1998
	A9	6,140,226	10/31/2000	Grill, et al.	438	637	07/30/1998
	A10	6,103,456	08/15/2000	Tobben, et al.	430	317	07/22/1998
	A11	6,054,379	04/25/2000	Yau, et al.	438	623	02/11/1998
	A12	5,926,740	07/20/1999	Forbes, et al.	438	763	10/27/1997
	A13	5,869,396	02/09/1999	Pan, et al.	438	647	07/15/1996
	A14	5,818,071	10/06/1998	Loboda, et al.	257	77	02/02/1995
	A15	5,817,579	10/06/1998	Ko, et al.	438	740	04/09/1997
	A16	5,817,572	10/06/1998	Chiang, et al.	438	624	12/18/1996

**Foreign Patent Documents**

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
	B1	0 725 440	08/07/1996	EP	H01L	23/532	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B2	0 613 178	02/22/1994	EP	H01L	21/90	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B3	99/33102	07/01/1998	WO	H01L	21/767	<input type="checkbox"/>	<input checked="" type="checkbox"/>

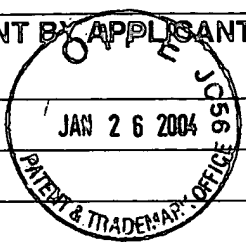
**OTHER ART**

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
	C1	Written Opinion from PCT/US99/22424, Dated April 5, 2001.
	C2	PCT International Search Report for PCT/US99/22425, Dated February 2, 2000.

Examiner	Date Considered
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

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(Use several sheets if necessary)		Filing Date	Group
Examiner Unknown		October 9, 2003	Unknown

**U.S. Patent Documents**

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
	A17	5,789,776	08/04/1998	Lancaster, et al.	257	296	09/18/1996
	A18	5,789,316	08/04/1998	Lu	438	638	03/10/1997
	A19	5,780,163	07/14/1998	Camilletti, et al.	428	446	06/05/1996
	A20	5,776,235	07/07/1998	Camilletti, et al.	106	287.1	10/04/1996
	A21	5,741,626	04/21/1998	Jain, et al.	430	314	04/15/1996
	A22	5,730,792	03/24/1998	Camilletti, et al.	106	287.14	10/04/1996
	A23	5,711,987	01/27/1998	Bearinger, et al.	427	7	10/04/1996
	A24	5,710,067	01/20/1998	Foote, et al.	437	238	06/07/1995
	A25	5,691,209	11/25/1997	Liberkowski	437	7	10/15/1996
	A26	5,658,834	08/19/1997	Dowben	438	478	11/17/1995
	A27	5,641,607	06/24/1997	Ogawa, et al.	430	272.1	09/28/1995
	A28	5,591,566	01/01/1997	Ogaw	430	325	06/07/1995
	A29	5,565,084	10/15/1996	Lee, et al.	205	646	06/07/1995
	A30	5,468,978	11/21/1995	Dowben	257	258	07/07/1993
	A31	5,465,680	11/14/1995	Loboda	117	84	07/01/1993
	A32	5,401,613	03/28/1995	Brewer, et al.	430	323	02/12/1992

**OTHER ART**

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
	C3	Ogawa, et al., "Novel ARC Optimization Methodology for KrF Excimer Laser Lithography at Low K Factor", Proceedings of the SPIE. Optical/Laser Microlithography Vol. 1674, 1992, pages 362-375.
	C4	Dijkstra, et al., "Optimization of Anti-Reflection Layers for Deep UV Lithography", Proceedings of SPIE Optical Laser Microlithography, Bellingham, SPIE, Vol. 1927, pages 275-286.
	C5	PCT International Search Report for PCT/US99/22424, Dated March 9, 2000.
	C6	PCT International Search Report for PCT/US99/22317, Dated March 21, 2000.

Examiner

Date Considered

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